EFS-Web Receipt date: 02/27/2008

DOCKET NO.: 270625US0PCT

IN THE UNITED STATES PATENT AND TRA

IN RE APPLICATION OF:

KENJI SUZUKI ET AL

: EXAMINER: TESKIN, FRED M.

SERIAL NO.: 10/532,244

SERIAL NO.: 10/332,244

FILED: APRIL 22, 2005

: GROUP ART UNIT: 1796

FOR: CURABLE RESIN COMPOSITION

AND FLEXOGRAPHIC PLATE MATERIAL USING THE SAME

CONSIDERED: /FT/

as to arguments;

evidenciary submissions not

considered.

REQUEST FOR RECONSIDERATION

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR:

OK to enter rea for recon,

In response to the Office Action dated November 27, 2007, reconsideration and allowance are respectfully requested in view of the following remarks.

Claims 1 and 3-5 are pending.

Rejection Under 35 U.S.C. §103

The Office Action rejects claims 1 and 3-5 under 35 U.S.C. §103(a) over U.S. Patent No. 5,250,389 to Nakamura et al. ("Nakamura") in view of U.S. Patent No. 4,230,836 to Canterino ("Canterino"), EP 0 013 139 to Arbit ("Arbit") or Weir, "Photolysis of Poly(pmethylstyrene)," J. App. Poly. Sci. 17: 401-419 (1973) ("Weir"). Applicants respectfully traverse the rejection.

Claim 1 recites "[a] cured material, obtained by <u>irradiating a curable resin</u>

composition with an active energy ray so that a moiety of a polymer block A contained in the